

Semiconductors

Gas flow rate controls

Instrumentation for sputtering systems

# More effective design of sputtering systems



Vacuum equipment

Process sensor Digital Mass Flow Controller

Model No. F4H

Product name

# **Current Situation**

- Countermeasures are implemented for plasma power supply noise.
- SP and PV are transmitted through analog wiring.
- Mass flow controllers are selected separately for each process.
- Wiring space must be reserved.

**Current Issues** 

Process and

equipment name

- Adding anti-noise components takes time and effort.
- The wiring is complicated because of the analog circuit design and the large number of wires.
- Spare parts management is complicated because controllers change when the process is adjusted.
- Structural design to leave space for wiring is troublesome.



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### Solutions



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